Fermilab

The Role of Oxygen Concentration in Enabling High Gradients in Niobium SRF Cavities

SRF 2021

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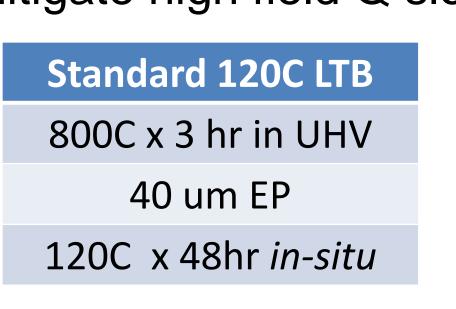
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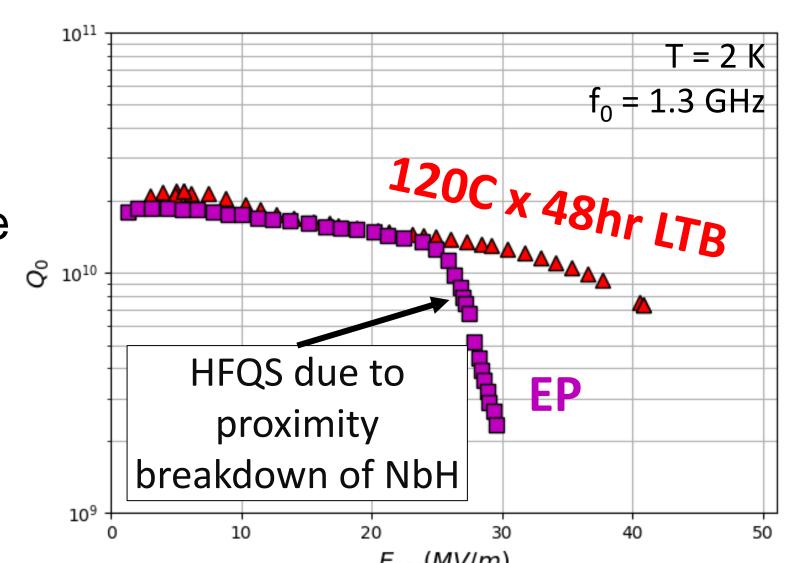
1. Introduction

We studied the role of O concentration with depth in the SRF cavities. An ensemble of electropolished 1.3 GHz single-cell cavities, all of which initially showed high field Q-slope (HFQS), was subjected to sequential testing and treatment with in-situ low temperature baking at various temperatures. We find that gradually increasing the integrated bake duration causes (i) an increase in the onset of HFQS until it is absent up to quench (ii) a nonmonotonic relationship with the quench field with a peak near ~90 nm (iii) an evolution of the R_{BCS} toward a non-equilibrium behavior that drives anti-Q slope. One possible driver for the observed phenomena stems from the diffusion of O from the oxide. Our findings support the hypothesis that the *mitigation of* HFQS that arises from 120 C in-situ LTB is mediated by the diffusion of O from the native oxide which prevents the precipitation of proximity-coupled nano-hydrides, in turn enabling higher quench fields. The observed decrease in quench field for cavities in which O has been diffused >90 nm from the RF surface may be due to a reduction of the field limit in the SS bilayer structure. We also suggest that the observed evolution of R_{BCS} occurs due to the absence of proximity coupled inclusions, bringing about non-equilibrium effects.

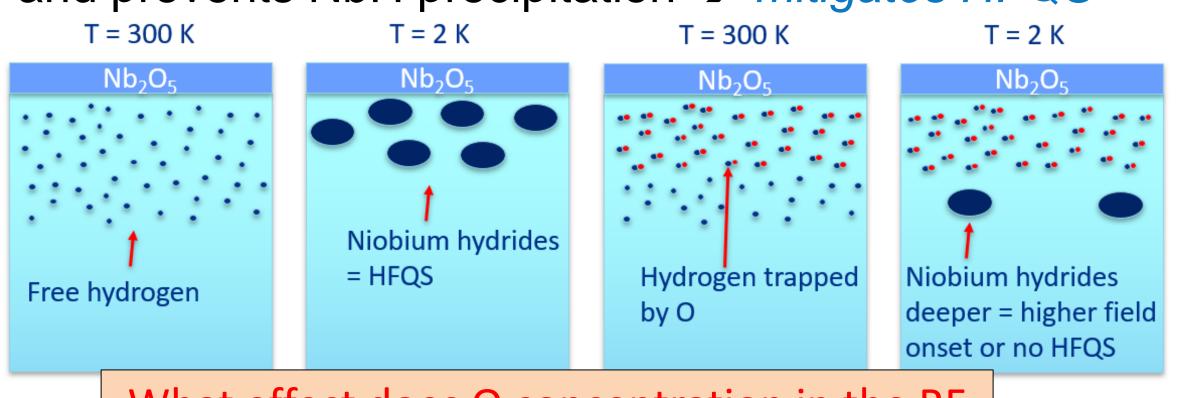
2. Model for Low T Baking

The standard 120C x 48 hr *in-situ* low temperature bake is well known to mitigate high field Q slope





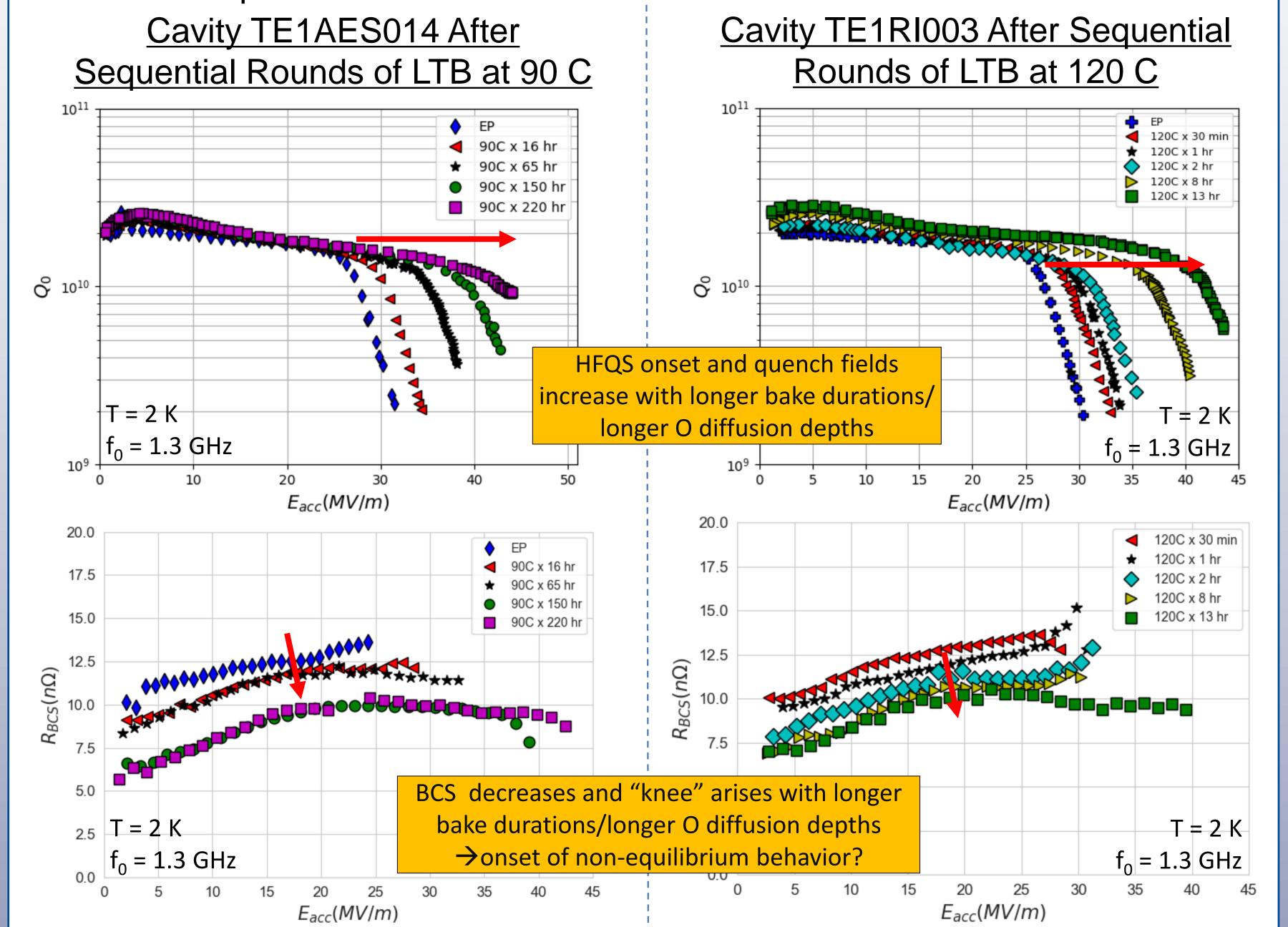
Recent work by Romanenko¹ suggests that *in-situ* LTB diffuses O from native oxide according to Fick's law, captures H, and prevents NbH precipitation → *mitigates HFQS*

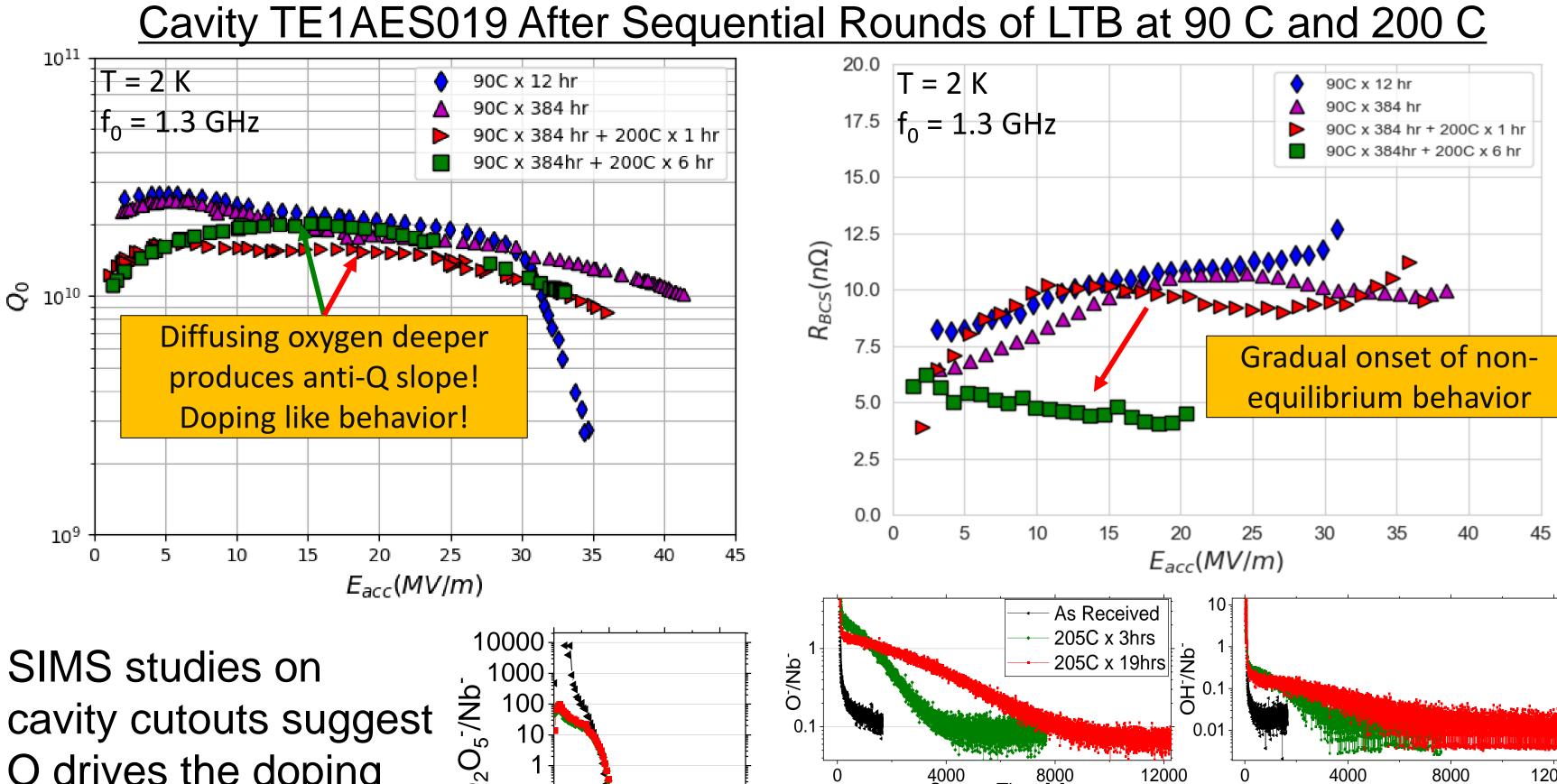


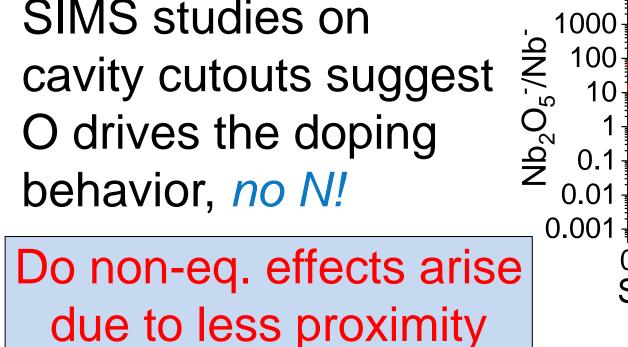
What effect does O concentration in the RF layer have on SRF cavity performance?

3. Experimental

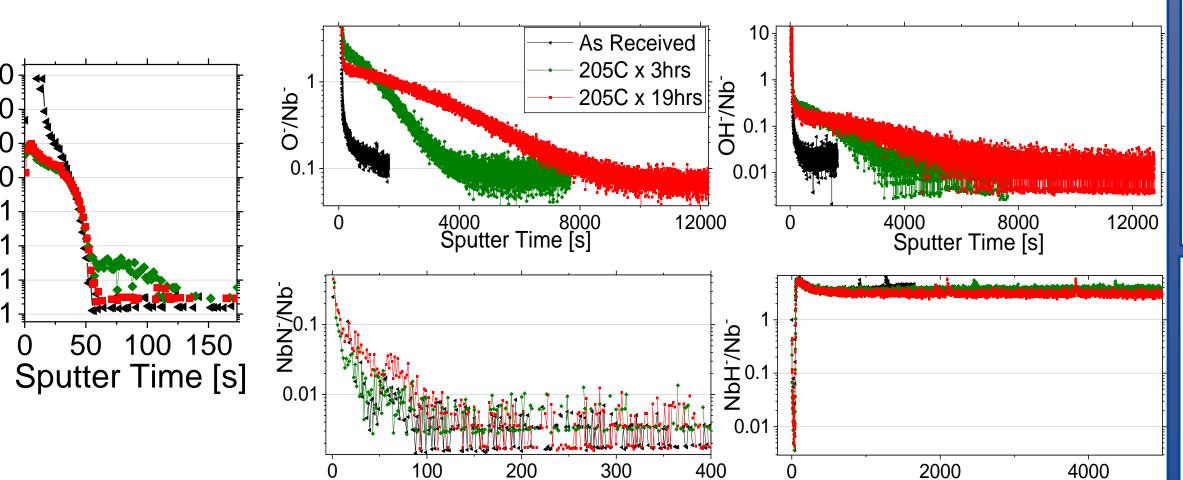
An ensemble of 1.3 GHz TESLA Nb cavities were subjected to *sequential insitu low temperature baking* at 90C, 120C, 150C, 160C, or 200C and tested after each step.







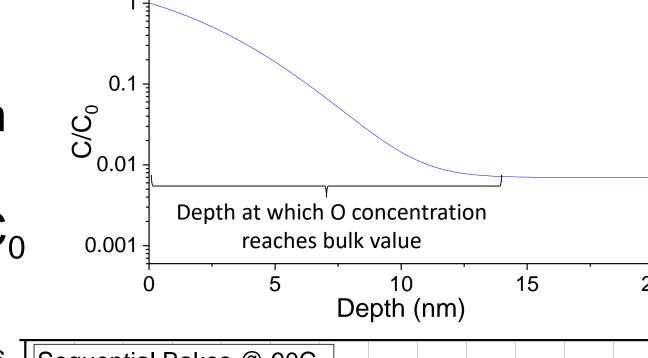
coupling to NbH?



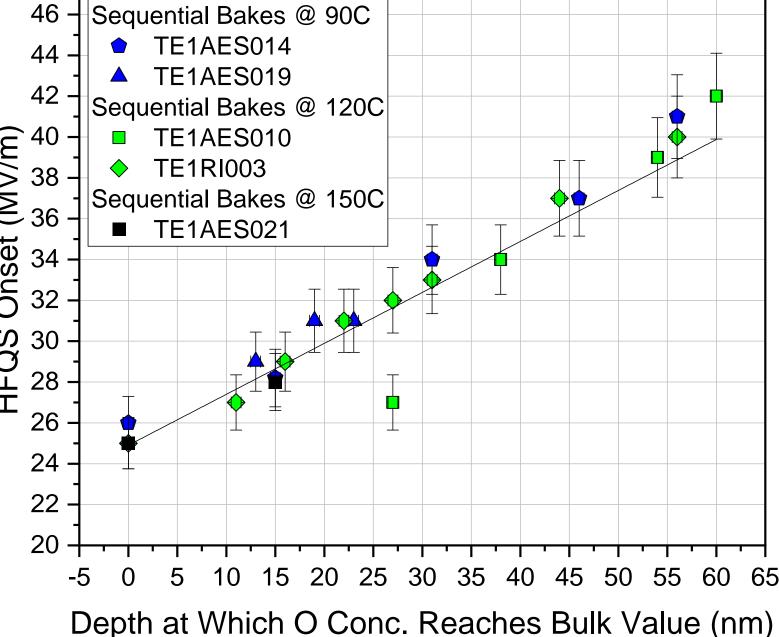
Sputter Time [s]

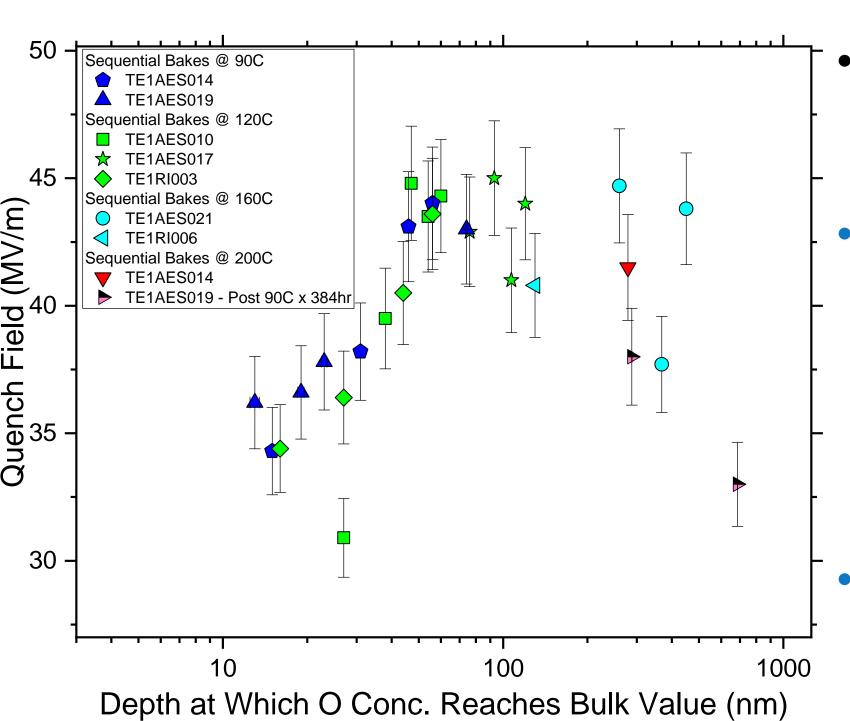
4. Trends w/ O Diffusion Depth

 O diffusion in Nb well modelled by Fick's law with concentration at surface constant at solubility limit C₀



- HFQS onset varies
 linearly with depth to
 which O diffuses
- Supports Romanenko 53 model → smaller/fewer 23 hydrides yield higher onset





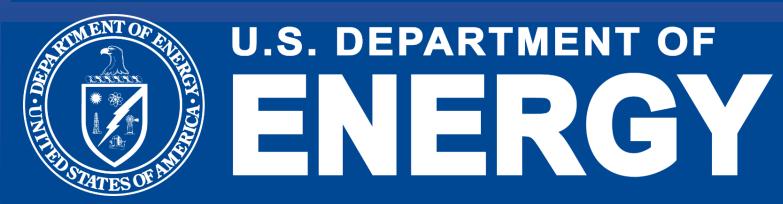
HFQS mitigation by
O diffusion enables
larger quench fields
Quench field
decreases when O
diffuses >90 nm,
may be due to
decrease of field
limit of SS bilayer²
Interplay of thermomagnetic and
magnetic quench?

5. Conclusions

- O diffusion plays a key role in the mitigation of HFQS and in enabling high quench fields in SRF cavities
- Peak *quench fields* achieved when diffused *O extends* ~90 nm from RF surface
- Diffusing O deep toward bulk may bring about nonequilibrium behavior in R_{BCS} and suggests "Oxygen doping" → anti-Q slope behavior may occur when proximity coupling and inelastic scattering are low

6. References

[1] A. Romanenko *et al.*, Proc. of SRF'19, THP014 [2] T. Kubo, SUST **30**, 023001 (2017)



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